2018년 2월 6일(화), 14:10-15:55 Room K (육백II, 6층)

Q. Metrology, Inspection, and Yield Enhancement 분과

[TK2-Q] Nanoanalysis

좌장: 박주철 센터장(구미전자정보기술원), 양준모 박사(나노종합기술원)

TK2-Q-1 14:10-14:25	Dynamic Thin Film Thickness Measurement based on Snapshot Spectro- Ellipsometry Vamara Dembele ¹ , Inho Choi ¹ , Madhan Jayakumar Paul ¹ , Sukhyun Choi ¹ , Junho Kim ¹ , Won Chegal ² , and Daesuk Kim ¹ ¹ Division of Mechanical System Engineering, Chonbuk National University, ² Advanced Instrumentation Institute, Korea Research Institute of Standards & Science
TK2-Q-2 14:25-14:55	[초청] Strain-Engineering in Advanced CMOS Structures Dae-Hong Ko Department of Materials Science and Engineering, Yonsei University
TK2-Q-3 14:55-15:25	[초청] Applications of TEM Electron Energy-Loss Spectroscopy (EELS) Analysis for Materials in Semiconductor Devices Jucheol Park, Jeong Eun Chae, Ji-Soo Kim, SangYeol Nam, and Min-Soo Kim Materials Characterization Center, Gumi Electronics & Information Technology
TK2-Q-4 15:25-15:40	Wafer 표면 Roughness에 따른 Thermal Oxide 영향 연구 정성우, 박정길, 김자영, 강희복 <i>SK Siltron</i>
TK2-Q-5 15:40-15:55	Detection of Metal Contamination in the Layer of Silicon Wafers Seung-Ik Jo, Ji-Yeon Lim, Sung-wook Lee SK Siltron
TK2-Q-6 15:55-16:10	Development of Interatomic Potentials in Si-O-F Systems Changhoon Heo ¹ , Hae-won Choi ¹ , In-ki Jeong ² , and Young-gui Yoon ² ¹ SEMES R&D Center, ² Department of Physics, Chung-Ang University